



公司簡介

MOCVD 創造世界級之競爭力

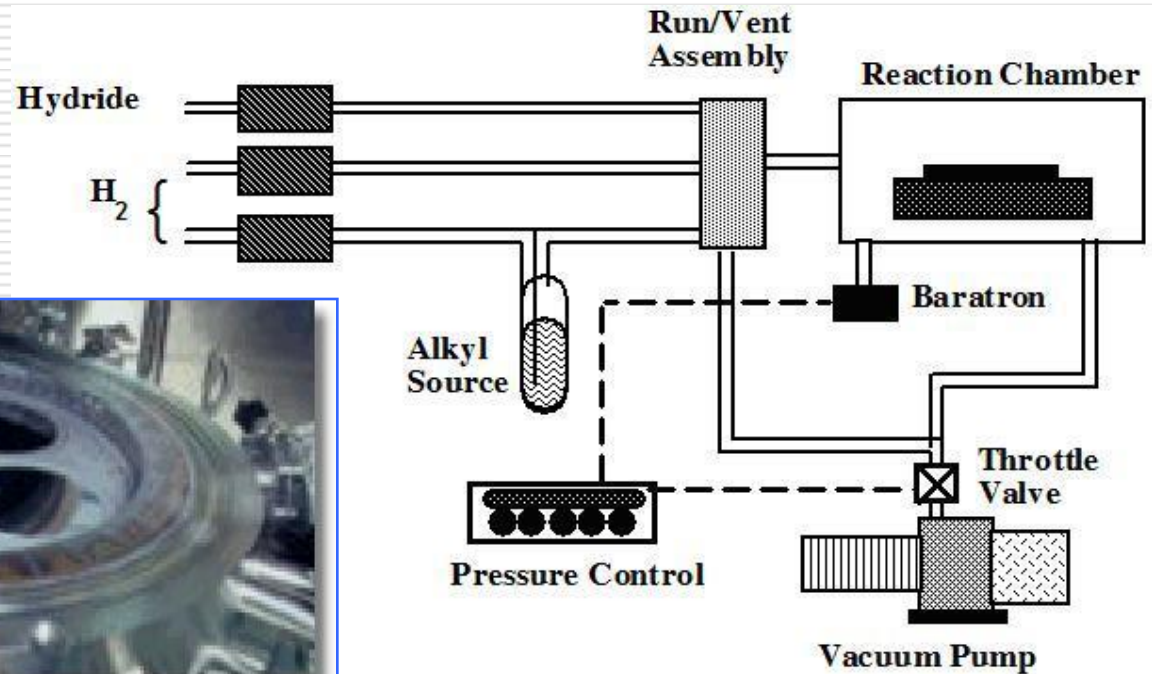




核心技術

MOCVD (有機金屬氣相沉積法)

- Metal Organic Chemical Vapor Deposition





核心技術

生產
機台

MOCVD有機金屬化學氣相沉積法
Metal Organic Chemical Vapor Deposition

生產
方式

透過有機金屬化學氣相沉積法，在基板上生長半導體薄膜的方式，同時透過機台即時監控，精確控制磊晶層，完成砷化鎵、磷化銦、氮化鎵等不同產品磊晶片生產。

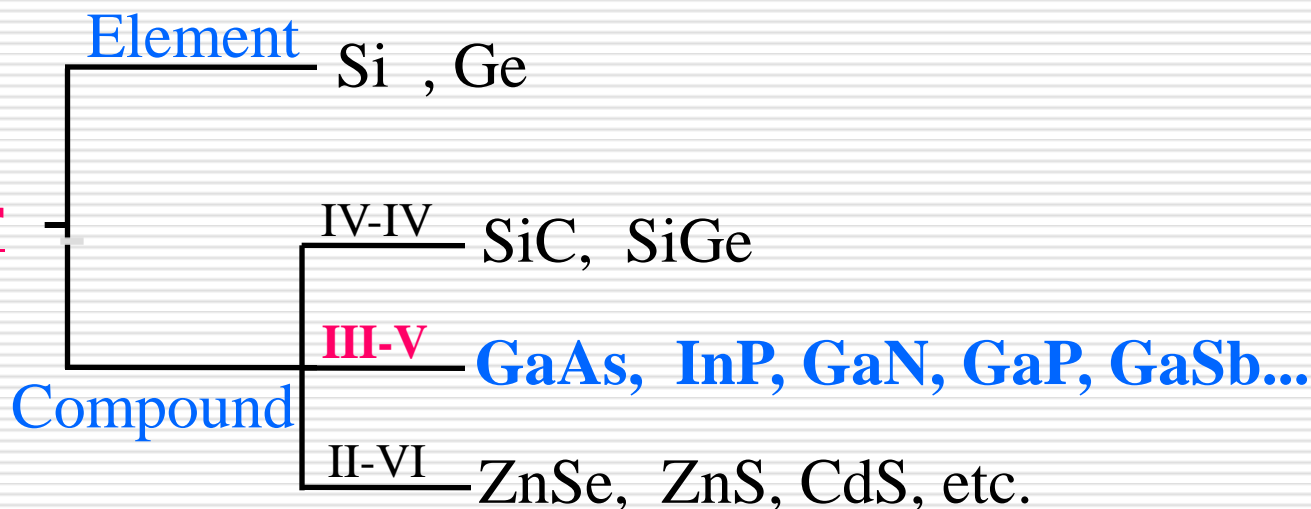
生產
原理

磊晶層是由MOCVD在腔體中加熱基板，一個原子層，層層堆疊，行成磊晶層。



半導體分類 (依使用材料)

Semiconductor



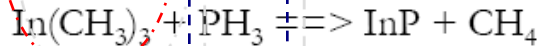
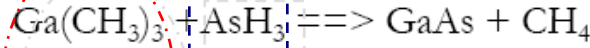
Period	Column II	III	IV	V	VI
2	Be 鈹 Beryllium	B 硼 Boron	C 碳 Carbon	N 氮 Nitrogen	O 氧 Oxygen
3	Mg 鎂 Magnesium	Al 鋁 Aluminum	Si 矽 Silicon	P 磷 Phosphorus	S 硫 Sulfur
4	Zn 鋅 Zinc	Ga 鎵 Gallium	Ge 鍺 Germanium	As 砷 Arsenic	Se 硒 Selenium
5	Cd 鎘 Cadmium	In 銦 Indium	Sn 錫 Tin	Sb 銻 Antimony	Te 碲 Tellurium
6	Hg 汞 Mercury	Tl 鉍 Thallium	Pb 鉛 Lead		

- 二元化合物 Binary : GaAs, InP, GaP, GaN, etc.
- 三元化合物 Ternary : InGaAs, InGaP, AlGaAs, etc.
- 四元化合物 Quaternary : AlGaInP, InGaAsP, etc.
- 五元化合物 Pentanary : AlGaInAsN, etc.



磊晶過程中之化學反應

化學反應式：



主要原物料：

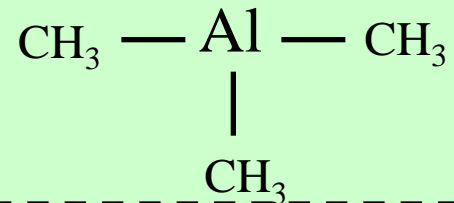
MO Source + **Hydride** + Carrier Gas : **H₂**

- TEAl : Tri-ethyl-Aluminum (C₂H₅)₃Al
- TMGa : Tri-Methyl-Gallium (CH₃)₃ Ga
- TMIn : Tri-Methyl-Indium (CH₃)₃In
- DETe : Di-ethyl-Tellurium (C₂H₅)₂Te
- DEZn : Di-ethyl-Zinc (C₂H₅)₂Zn
- CP₂Mg : Bis (cyclo-penta-dienyl) -Magnesium 環戊二烯鎂

- AsH₃ : Arsine
- PH₃ : Phosphine
- SiH₄ : Silane
- Si₂H₆ : Disilane
- H₂Se : Hydrogen Selenide
- CBr₄ : Carbon Tetrabromide

TMAI Tri - Methyl - Aluminum (CH₃)₃Al

三 甲 基 鋁





化合物半導體材料特性

1. High Electron Mobility 高電子移動速率 (5.7x higher than CMOS)
2. High Frequency Response 高頻率響應
3. Wide Band Width 寬幅之頻寬
4. High Linearity 高線性度
5. High Power 高功率
6. Alternative Choice of Material 材料選擇多元性
7. 抗輻射

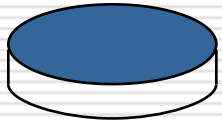
適用於無線通訊、光通訊、雷射



產業供應鏈

Sumitomo, Freiberg, AXT

2~6 "GaAs Substrate

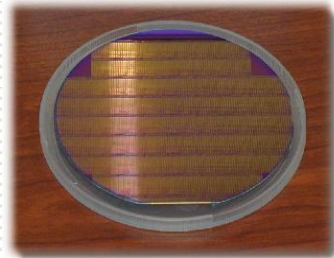


GaAs Epi- Wafer
磊晶片



IDM : Qorvo, Avago,
Skyworks

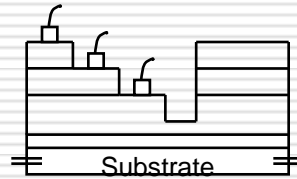
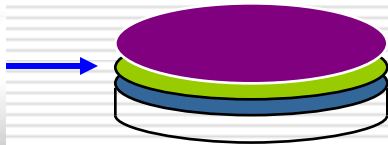
Microelectronics
IC Process



Wireless
Communication



MOCVD Reactor



Foundry :

WIN, AWSC,
GCS



IC Package & Testing



2019年-2022年前三季度损益情形

	2022Q1 ~ Q3	%	2021	%	2020	%	2019	%
Revenue	2,097,562	100.00%	3,608,521	100.00%	2,645,003	100.00%	2,530,909	100.00%
Gross margin	887,994	42.33%	1,519,713	42.11%	1,114,404	42.13%	1,034,272	40.87%
Operating Profit	516,679	24.63%	1,056,519	29.28%	687,515	25.99%	648,983	25.64%
Non-operating income & expense	100,058	4.77%	-3,842	-0.11%	-40,212	-1.52%	-20,380	-0.81%
Tax	-109,042	-5.20%	-197,596	-5.48%	-114,715	-4.34%	-114,278	-4.52%
Net income	507,695	24.20%	855,081	23.70%	532,588	20.14%	514,325	20.32%
EPS	2.75		4.62		2.88		2.79	



2022 微電子產品 Outlook

5G Mobile Penetration



WiFi6 / 6E



IoT Smart Link



**Micro
Electronics**

V2X PA



LEO Satellite



5G Base Station



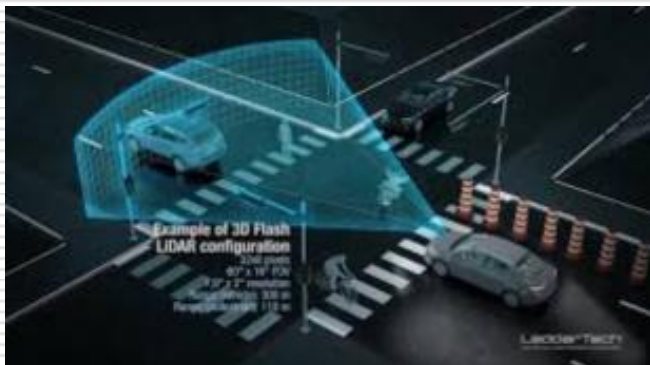
Military





2022 光電子產品 Outlook

Car LiDAR



AR / VR Sensing



Opto
electron
ics

Robot Vacuum Sense



Special Heat/IR Imaging



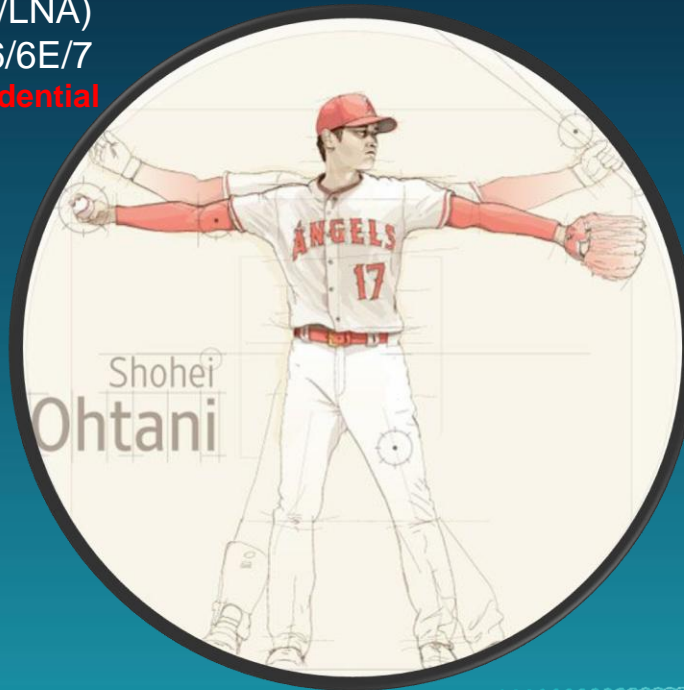
AR / VR

Emitter: VCSEL
Detector: PD
Eye-safety

Wireless

HBT (PA)
pHEMT (Switch/LNA)
WiFi 6/6E/7

VPEC Proprietary and Confidential



LiDAR Turnkey Solution

Emitter: VCSEL, EEL
Detector: PD, APD
Eye-safety (1400nm ~ 1600nm)
Long Range Detection (400m)

V2X

HBT (PA)
pHEMT (Switch/LNA)
WiFi 6/6E/7

